AMENDMENTS TO SPECIFICATION

Please amend the paragraph beginning at page 11, line 18 as follows:

At box 730, a database is searched for all interlayer defect pairs consistent with the restrictions previously at box 710 and box 720. The process of box 730 may be performed after at least two inspections have been performed on the wafer. After locating all defect pairs that satisfy the restrictions previously selected (Xmax, Ymax, ~~Xmin, Ymin~~ Xint, Yint), the offsets ΔX and ΔY in the coordinates of these defect pairs are calculated and saved for later use.

Please amend the paragraph beginning at page 13, line 4 as follows:

The histograms of distances between pairs seen on a wafer for the x-coordinate and y-coordinate are shown in FIGS. 5 and 6, respectively. Referring now to FIG. 5, there is shown an exemplary histogram that may be generated during an inspection process undertaken on wafer ~~10~~ 100. As shown in FIG. 5, there is a peak value 510 in the distribution of differences in the region between 0 and +2μm.

Please amend the abstract as follows:

A method for determining between at least three origins of a coordinate system used for at least three different defect inspection spaces. The method comprises: collecting multiple sets of data spanning defect inspection spaces; filtering the data sets to remove points that introduce noise into correlation calculations; determining whether different data sets show correlation; selecting pairs of data sets showing correlation greater than or equal to a metric; and calculating coordinate offsets of at least three origins based on the selected pairs of data sets.

~~It is emphasized that this abstract is provided to comply with the rules requiring an abstract that will allow a searcher or other reader to quickly ascertain the subject matter of the technical disclosure. It is submitted with the understand that it will not be used to interpret or limit the scope or meaning of the claims. 37 CFR 1.72(b).~~